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YAO-3950

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Yoshihisa Nagano et al.

: Art Unit: 2815

Serial No.:

09/103,873

: Examiner: J. Diaz

Filed:

June 24, 1998

For: SEMICONDUCTOR DEVICE AND

METHOD FOR FABRICATING THE SAME

AMENDMENT

- 1 Assistant Commissioner for Patents
- 2 Washington, DC 20231
- 3 SIR:
- Responsive to the Official Action dated April 9, 2002, please amend
- 5 the above-identified application as follows:
- 6 CLAIMS:

Please replace claims 1, 30 and 31 with the following amended

8 claims:

1. (As Amended) A semiconductor device, comprising:

a capacitor provided on a supporting substrate having an integrated circuit thereon and including a lower electrode, a dielectric film, and an upper electrode, said dielectric film being formed from either a dielectric material having

a high dielectric constant or a ferroelectric material;

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189 files interlayer insulating film provided so as to directly cover the

- 15 capacitor;
- a first interconnect selectively provided on the first interlayer
- insulating film and electrically connected to the integrated circuit and the capacitor
- through a first contact hole formed in the first interlayer insulating film;
- a second interlayer insulating film having a tensile stress provided so
- as to directly cover the first interconnect and the first interlayer insulating film;

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